



Advanced Workshop on Semiconductor Manufacturing

21st May to 3rd June 2026

Centre for Nano Science and Engineering
Indian Institute of Science, Bangalore-560012

Tel: 080-2293 3542 Email: workshop.cense@iisc.ac.in



Program Schedule

21st May 2026, Thursday (Online mode – Microsoft Teams)

Morning Session Link

Time	Event
10:00 AM – 10:30 AM	Introductory Session – Prof. Sushobhan Avasthi & Ms. Sabiha Sultana
10:30 AM – 11:30 AM	NNfC Safety Protocol – Ms. Shruti Hegde
11:30 AM – 12:15 PM	Introduction to Wet Etch Bay – Dr. Rekha M
12:15 PM – 1:00 PM	Introduction to Furnaces – Mr. Saleem Ahmed B

1:00 PM – 2:00 PM: Lunch Break

Afternoon Session Link

Time	Event
2:00 PM – 3:00 PM	Introduction to Thin Films – Mr. Chandan H B
3:00 PM – 4:00 PM	Introduction to Lithography – Mr. Ajeya Shettar
4:00 PM – 4:45 PM	Introduction to Dry Etch – Ms. Vidyashree K h
4:45 PM – 5:30 PM	Introduction to MOSFET Module – Ms. Sabiha Sultana

22nd May 2026, Friday (Online mode – Microsoft Teams)

Morning Session Link

Time	Event
9:30 AM – 10:15 AM	Introduction to Electrical Characterization – Mr. Kumar M P
10:15 AM – 11:00 AM	Introduction to AFM – Mr. Vishnuteerth
11:00 AM – 12:00 PM	Introduction to SEM – Dr. Rashmitha Keshava Devadiga
12:00 PM – 1:00 PM	Introduction to FTIR / UV Vis Spectroscopy – Ms. Sinchana R & Ms. Bindhu V

1:00 PM – 2:00 PM: Lunch Break

Afternoon Session Link

Time	Event
2:00 PM – 3:00 PM	Introduction to FIB – Dr. Nagabhushan J Choudhari
3:00 PM – 4:00 PM	Introduction to TEM – Mr. Ambresh M



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Holiday – 23rd May 2026, Saturday

Holiday – 24th May 2026, Sunday

25th May 2026, Monday

Time	Event
8:30 AM – 9:00 AM	Registration for the Workshop (Ground Floor CeNSE Seminar Hall)
9:00 AM – 9:30 AM	Briefing & Introductory Session

MOSFET – Batch 1 09:30 AM – 1:00 PM	MOSFET - Batch 2 9:30 AM – 1:00 PM	MOSFET - Batch 3 9:30 AM – 1:00 PM	MOSFET - Batch 4 9:30 AM – 1:00 PM
Fabrication Session - 1 RCA Oxidation Ellipsometer (NNFC)	Characterization Session - 1 SEM / FIB (MNCF)	Characterization Session - 1 AFM / FTIR / UV-Vis spectroscopy (MNCF)	Lab Visit: Gas Sensor Lab (Second Floor SF-31)

1:00 PM – 2:00 PM: Lunch Break (Ground Floor Parking Area)

MOSFET - Batch 1 2:00 PM – 5:00 PM	MOSFET - Batch 2 2:00 PM – 5:00 PM	MOSFET - Batch 3 2:00 PM – 5:00 PM	MOSFET - Batch 4 2:00 PM – 5:00 PM
Characterization Session - 1 SEM / FIB (MNCF)	Fabrication Session - 1 RCA Oxidation Ellipso (NNFC)	Lab Visit: Gas Sensor Lab (Second Floor SF-31)	Characterization Session - 1 Probe Station 2 (MNCF)



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26th May 2026, Tuesday

MOSFET - Batch 1 9:30 AM – 1:00 PM	MOSFET - Batch 2 9:30 AM – 1:00 PM	MOSFET - Batch 3 9:30 AM – 1:00 PM	MOSFET - Batch 4 9:30 AM – 1:00 PM
Fabrication Session - 2 Litho 1 SiO ₂ wet etch Diffusion (NNFC)	Characterization Session - 2 AFM / FTIR / UV-Vis spectroscopy (MNCF)	Fabrication Session - 1 RCA Oxidation Ellipso (NNFC)	Characterization Session - 2 SEM / FIB (MNCF)

1:00 PM – 2.00 PM: Lunch Break (Ground Floor Parking Area)

MOSFET - Batch 1 2:00 PM – 5:00 PM	MOSFET - Batch 2 2:00 PM – 5:00 PM	MOSFET - Batch 3 2:00 PM – 5:00 PM	MOSFET - Batch 4 2:00 PM – 5:00 PM
Characterization Session - 2 AFM / FTIR / UV-Vis spectroscopy (MNCF)	Fabrication Session - 2 Litho 1 SiO ₂ wet etch Diffusion (NNFC)	Characterization Session - 2 SEM / FIB (MNCF)	Fabrication Session - 1 RCA Oxidation Ellipso (NNFC)

Holiday – 27th May 2026, Wednesday

28th May 2026, Thursday

MOSFET - Batch 1 9:30 AM – 1:00 PM	MOSFET - Batch 2 9:30 AM – 1:00 PM	MOSFET - Batch 3 9:30 AM – 1:00 PM	MOSFET - Batch 4 9:30 AM – 1:00 PM
Fabrication Session - 3 PSG etch+4pp ALD Al ₂ O ₃ Litho 2 SiO ₂ wet etch (NNFC)	Characterization Session - 3 Probe Station 2 (MNCF)	Fabrication Session - 2 Litho 1 SiO ₂ wet etch Diffusion (NNFC)	Characterization Session - 3 TEM (MNCF)

1:00 PM – 2.00 PM: Lunch Break (Ground Floor Parking Area)



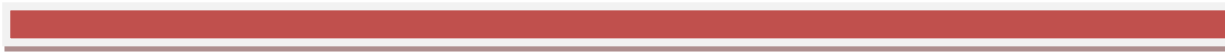
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MOSFET - Batch 1 2:00 PM – 5:00 PM	MOSFET - Batch 2 2:00 PM – 5:00 PM	MOSFET - Batch 3 2:00 PM – 5:00 PM	MOSFET - Batch 4 2:00 PM – 5:00 PM
Packaging Lab Session 1 (Third Floor TF-32)	Fabrication Session - 3 PSG etch+4pp ALD Al ₂ O ₃ Litho 2 SiO ₂ wet etch (NNFC)	Characterization Session - 3 TEM (MNCF)	Fabrication Session - 2 Litho 1 SiO ₂ wet etch Diffusion (NNFC)

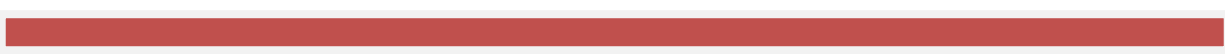


29th May 2026, Friday

MOSFET - Batch 1 9:30 AM – 1:00 PM	MOSFET - Batch 2 9:30 AM – 1:00 PM	MOSFET - Batch 3 9:30 AM – 1:00 PM	MOSFET - Batch 4 9:30 AM – 1:00 PM
Fabrication Session - 4 Metal dep Litho 3 (background) Metal dry etch Anneal (background) (MNCF)	Characterization Session - 4 TEM (MNCF)	Fabrication Session - 3 PSG etch+4pp ALD Al ₂ O ₃ Litho 2 SiO ₂ wet etch (NNFC)	Packaging Lab Session 1 (Third Floor TF-32)

1:00 PM – 2:00 PM: Lunch Break (Ground Floor Parking Area)

MOSFET - Batch 1 2:00 PM – 5:00 PM	MOSFET - Batch 2 2:00 PM – 5:00 PM	MOSFET - Batch 3 2:00 PM – 5:00 PM	MOSFET - Batch 4 2:00 PM – 5:00 PM
Characterization Session - 3 Probe Station 2 (MNCF)	Fabrication Session - 4 Metal dep Litho 3 (background) Metal dry etch Anneal (background) (NNFC)	Characterization Session - 4 Probe Station 2 (MNCF)	Characterization Session - 4 AFM / FTIR / UV-Vis spectroscopy (MNCF)





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Holiday – 30th May 2026, Saturday

Holiday – 31st May 2026, Sunday

1st June 2026, Monday

MOSFET - Batch 1 9:30 AM – 1:00 PM	MOSFET - Batch 2 9:30 AM – 1:00 PM	MOSFET - Batch 3 9:30 AM – 1:00 PM	MOSFET - Batch 4 9:30 AM – 1:00 PM
Lab Visit: Gas Sensor Lab (Second Floor SF-31)	Packaging Lab Session 1 (Third Floor TF-32)	Fabrication Session - 4 Metal dep Litho 3 (background) Metal dry etch Anneal (background) (NNFC)	Fabrication Session - 3 PSG etch+4pp ALD Al2O3 Litho 2 SiO2 wet etch (NNFC)

1:00 PM – 2:00 PM: Lunch Break (Ground Floor Parking Area)

MOSFET - Batch 1 2:00 PM – 5:00 PM	MOSFET - Batch 2 2:00 PM – 5:00 PM	MOSFET - Batch 3 2:00 PM – 5:00 PM	MOSFET - Batch 4 2:00 PM – 5:00 PM
Packaging Lab Session 2 (Third Floor TF-32)	Lab Visit: Gas Sensor Lab (Second Floor SF-31)	Packaging Lab Session 1 (Third Floor TF-32)	Fabrication Session - 4 Metal dep Litho 3 (background) Metal dry etch Anneal (background) (NNFC)



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2nd June 2026, Tuesday

MOSFET - Batch 1 9:30 AM – 1:00 PM	MOSFET - Batch 2 9:30 AM – 1:00 PM	MOSFET - Batch 3 9:30 AM – 1:00 PM	MOSFET - Batch 4 9:30 AM – 1:00 PM
Characterization Session - 4 TEM (MNCF)	Packaging Lab Session 2 (Third Floor TF-32)	Presentation by participants (CeNSE Seminar Hall)	Presentation by participants (CeNSE Seminar Hall)

1:00 PM – 2:00 PM: Lunch Break (Ground Floor Parking Area)

MOSFET - Batch 1 2:00 PM – 5:00 PM	MOSFET - Batch 2 2:00 PM – 5:00 PM	MOSFET - Batch 3 2:00 PM – 5:00 PM	MOSFET - Batch 4 2:00 PM – 5:00 PM
Presentation by participants (CeNSE Seminar Hall)	Presentation by participants (CeNSE Seminar Hall)	Packaging Lab Session 2 (Third Floor TF-32)	Packaging Lab Session 2 (Third Floor TF-32)

3rd June 2026, Wednesday

Time	Event
10:00 AM – 11:00 AM	Fabrication & Characterization Quiz Session (CeNSE Seminar Hall)
11:00 AM – 12:00 PM	Interaction with Candidates + Next Steps
12:00 PM – 1.00 PM	Feedback, Valedictory & Concluding Session
1:00 PM – 2:00 PM	Lunch Break